RADIATION SENSITIVE SILICON-CONTAINING NEGATIVE RESISTS AND USE THEREOF

ABSTRACT OF THE DISCLOSURE

- 5 A negative resist composition, comprising:
 - (a) silicon-containing polymer with pendant fused moieties selected from the group consisting of fused aliphatic moieties, homocyclic fused aromatic moieties, and heterocyclic fused aromatic and sites for reaction with a crosslinking agent,
 - (b) an acid-sensitive crosslinking agent, and
- 10 (c) a radiation-sensitive acid generator is provided. The resist composition is used to form a patterned material layer in a substrate.